L Number	Hits	Search Text	DB	Time stamp
1	2898	plasma adj density	USPAT	2004/02/05
2	1911	(plasma adj density) and semiconductor	USPAT	09:08 2004/02/05
3	1018	((plasma adj density) and semiconductor) and (oxygen or O?sub.2)	USPAT	09:09 2004/02/05 09:09
4	545	(((plasma adj density) and semiconductor) and (oxygen or O?sub.2)) and	USPAT	2004/02/05
5	12	(photo\$1resist or resist) Ishihara-Shigenori.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/02/05 11:00
8	2225	(resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)	IBM_TDB USPAT	2004/02/05
9	6		USPAT	11:31 2004/02/05 11:02
10	1343		USPAT	2004/02/05
14	1100	(((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000	USPAT	2004/02/05
15	578	((((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000) and (dope or doping or dopant or implant\$3 or implantation)	USPAT	2004/02/05
16	142	(((((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000) and (dope or doping or dopant or implant\$3 or implantation)) and (photo\$1resist or resist or photo\$1sensitive).ab.	USPAT	2004/02/05
17	5	("4511430" "5226056" "5503964" "5795831" "5811358").PN.	USPAT	2004/02/05
18	15		USPAT	11:27 2004/02/05 11:30
19	80	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and ((fluorine\$ or CF?sub.4 or SF?sub.6) with (percent or "%" or percentage))	USPAT	2004/02/05
20	71	(((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and ((fluorine\$ or CF?sub.4 or SF?sub.6) with (percent or "%" or percentage))) and @ay<=1999	USPAT	2004/02/05
-	3838	(resist or photo\$1resist) same (ash or ashing)	USPAT	2004/01/14
	2210	(resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)	USPAT	2004/02/05 11:01
-	2412	(resist or photo\$1resist) same (ash or ashing) same (oxygen or 0?sub.2 or CO or NO or (nitrogen adj oxide))	USPAT	2004/01/14
_	1045	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)	USPAT	2004/01/14 13:45

	0.45			
_	247	1 (/ (D D T T T T T T T T T T T T T T T T T	USPAT	2004/01/21
	İ	O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or		15:22
		ion\$limplant\$3 or doped or doping or		
		dopant)) and plasma) and (resist or		
		photo\$1resist or photo\$1sensitive or		
		organic		
-	238		USPAT	2004/01/21
		0?sub.2) with (hydrogen\$ or H?sub.2) with		15:21
		(fluorine\$))) and (implant\$3 or		
		ion\$1implant\$3 or doped or doping or		
		dopant)) and plasma) and (resist or		
		<pre>photo\$1resist or photo\$1sensitive or organic)) and @ay<=2001</pre>		
-	206	(((semiconductor and ((oxygen\$ or	11003 0	0004/04/05
		O?sub.2) with (hydrogen\$ or H?sub.2) with	USPAT	2004/01/21
		(fluorine\$))) and (implant\$3 or		15:23
		ion\$1implant\$3 or doped or doping or		
		dopant)) and plasma) and (resist or		ļ
		photo\$1resist or photo\$1sensitive)		
-	20	("4778536" "5100505" "5108542"	USPAT	2004/01/21
		"5147499" "5160765" "5200361"		15:43
		"5296093" "5298112" "5485754"		
		"5628871" "5693147" "5744192" "5773201" "5810929" "5814155"		
•		3773201 3810929* **5814155* "5851302" "5882489" "5895274"		
		"5925577" "6066508").PN.		
-	8	("5034086" "5226056" "5393374"	USPAT	2004/01/21
	1	"5567271" "5792314" "5902134"	ODERI	16:41
		"6024887" "6043004").PN.		10.11
-	3173	(resist or photo\$1resist or	USPAT	2004/02/02
		photo\$1sensitive) same (oxygen\$ or		11:02
l _	2039	O?sub.2) same (hydrogen\$ or H?sub.2)		
	2039	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or	USPAT	2004/02/02
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11:01
		plasma		
-	947	(((resist or photo\$1resist or	USPAT	2004/02/02
		photo\$1sensitive) same (oxygen\$ or	551111	11:01
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11.01
		plasma) and (fluorine or F?sub.2 or		1
· _	768	fluoride)		
]	/ 60	((((resist or photo\$1resist or	USPAT	2004/02/02
		<pre>photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and</pre>		11:06
		plasma) and (fluorine or F?sub.2 or		
		fluoride)) and ((oxygen\$ or O?sub.2) with		
		(hydrogen\$ or H?sub.2))		
-	515	(((((resist or photo\$1resist or	USPAT	2004/02/02
		photo\$1sensitive) same (oxygen\$ or		11:12
	l	0?sub.2) same (hydrogen\$ or H?sub.2)) and		
	ŀ	plasma) and (fluorine or F?sub.2 or		
		fluoride)) and ((oxygen\$ or O?sub.2) with		
i	ļ	(hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or		
ľ		ion\$limplant\$3)		
-	497	((((((resist or photo\$1resist or	USPAT	2004/02/02
		photo\$1sensitive) same (oxygen\$ or	ODIAL	11:05
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11.00
İ		plasma) and (fluorine or F?sub.2 or		
		fluoride)) and ((oxygen\$ or O?sub.2) with		
	j	(hydrogen\$ or H?sub.2))) and (implant\$3		
		or doping or dopant or doped or		
		ion\$1implant\$3)) and @ay<=2001		

-	474	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT	2004/02/02	٦
		photo\$1sensitive) same (oxygen\$ or		11:05	į
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		1	
		plasma) and (fluorine or F?sub.2 or			
		fluoride)) and ((oxygen\$ or O?sub.2) with		i	
		(hydrogen\$ or H?sub.2))) and (implant\$3			
		or doping or dopant or doped or			1
	1	ion\$limplant\$3)) and Gay<=2001) and		ļ	ſ
j _	301	semiconductor			
	301	<pre>(((((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or</pre>	USPAT	2004/02/02	
		Obside (oxygens or		11:13	ĺ
1		O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or			
		fluoride)) and ((oxygen\$ or O?sub.2) with			-
		(hydrogen\$ or H?sub.2))) and ((implant\$3			
		or doping or dopant or doped or			
		ion\$limplant\$3) same (resist or			- 1
		photo\$1resist or photo\$1sensitive))			1
_	163	(((((resist or photo\$1resist or	TTGD3 III	2004/2012	
		photo\$1sensitive) same (oxygen\$ or	USPAT	2004/02/02	
1		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11:13	-
		plasma) and (fluorine or F?sub.2 or	1		
		fluoride)) and ((oxygen\$ or O?sub.2) with			-
		(hydrogen\$ or H?sub.2))) and ((implant\$3			
		or doping or dopant or doped or	I		
		ion\$1implant\$3) with (resist or		1	
		photo\$1resist or photo\$1sensitive))			Ì
-	156	((((((resist or photo\$1resist or	USPAT	2004/02/02	
		photo\$1sensitive) same (oxygen\$ or	USPAT	2004/02/02	
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		11:14	-
		plasma) and (fluorine or F?sub.2 or			
	i	fluoride)) and ((oxygen\$ or O?sub.2) with			
		(hydrogen\$ or H?sub.2))) and ((implant\$3			
		or doping or dopant or doped or			
		ion\$1implant\$3) with (resist or			
		photo\$1resist or photo\$1sensitive))) and			
1		@ay<=2001			
-	145	(((((resist or photo\$1resist or	USPAT	2004/02/02	ı
		photo\$1sensitive) same (oxygen\$ or	OBLILL	11:14	
		O?sub.2) same (hydrogen\$ or H?sub.2)) and		*** ***	
		plasma) and (fluorine or F?sub.2 or			ı
İ		fluoride)) and ((oxygen\$ or O?sub.2) with			
		(hydrogen\$ or H?sub.2))) and ((implants3			
		or doping or dopant or doped or			ı
		ion\$limplant\$3) with (resist or		1	
		<pre>photo\$1resist or photo\$1sensitive))) and</pre>			
		@ay<=2000			ĺ
-	16	("4063803" "4201579" "4340456"	USPAT	2004/02/02	
	i	"4817558" "4990229" "5122251"		11:16	
I		"5262610" "5366557" "5397395"			ĺ
		"5429070" "5542559" "5625259"			
		"5747917" "5789322" "5824604"			
		"5895548").PN.			
_	8	("5034086" "5226056" "5393374"	USPAT	2004/02/02	
		"5567271" "5792314" "5902134"		11:35	
		"6024887" "6043004").PN.			ı

-	970	ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping	USPAT	2004/01/14 13:45
_	593	or dopant or implant or implanting or implanted)) and plasma ((((resist or photo\$1resist) same (ash or	Ист.	
į		ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or	USPAT	2004/01/14 13:47
		implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")		
-	402	<pre>(((((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and</pre>	USPAT	2004/01/14 13:49
		(doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or		
-	348	F?sub.2 or SF?sub.6) (((((resist or photo\$1resist) same (ash	USPAT	2004/01/14
		or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or		13:50
		implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6)) and @ay<=2000		
_	344	<pre>(((((((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and</pre>	USPAT	2004/01/14
		(doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6)) and @ay<=2000) and (boron or phosphorus or arsenic or As!)		
	101	(((((((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and	USPAT	2004/01/14 13:52
		(hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6)) and @ay<=2000) and (boron or phosphorus or arsenic or As!))		
-	14	and plasma.ab. ("4296146" "4778536" "4861424" "4944837" "5013366" "5037506" "5298112" "5382316" "5401322" "5403436" "5643474" "5651860"	USPAT	2004/01/14
_	657	"6024801" "6149828").PN. semiconductor and ((oxygen\$ or 0?sub.2) with (hydrogen\$ or H?sub.2) with	USPAT	2004/01/21 15:16
_	360	<pre>(fluorine\$)) (semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or</pre>	USPAT	2004/01/21 15:19
		<pre>ion\$1implant\$3 or doped or doping or dopant)</pre>		
_	322	<pre>((semiconductor and ((oxygen\$ or 0?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$limplant\$3 or doped or doping or</pre>	USPAT	2004/01/21 15:19
<u> </u>	L	dopant)) and plasma		